

CLAIMS

1. A wafer storage case of synthetic resin housing wafers, wherein a surface of the wafer storage case is coated with a coating layer of a coating agent to prevent dust generation from the surface.

2. The wafer storage case according to claim 1, wherein the coating agent is a surfactant.

3. A process for preventing dust generation of a wafer storage case comprising the steps of:

coating a surface of the wafer storage case of synthetic resin housing wafers with a coating agent;

drying the wafer storage case coated with the coating agent;

cleaning the dried wafer storage case using pure water such that a coating layer of the coating agent remains across the surface of the wafer storage case; and

drying the cleaned wafer storage case,

wherein dust generation from the surface of the wafer storage case is prevented by the coating layer of the coating agent.

4. A process for preventing dust generation of a wafer storage case comprising a step of:

coating a surface of the wafer storage case of synthetic resin housing wafers with a coating agent;

cleaning the wafer storage case using pure water such that a coating layer of the coating agent remains across the surface of the wafer storage case; and

drying the cleaned wafer storage case,

wherein dust generation from the surface of the wafer storage case is prevented by the coating layer of the coating agent.

5. The process for preventing dust generation of a wafer storage case according to claim 4, wherein the pure water used in the step of cleaning with the pure water such that the coating layer of the coating agent remains across the surface of the wafer storage case is pure water with a low specific resistance.

6. The process for preventing dust generation of a wafer storage case according to claim 5, wherein the pure water with a low specific resistance has a specific resistance of 10 MΩ-cm or less.

7. The process for preventing dust generation of a wafer storage case according to any of claims 3 to 6, wherein by immersing the wafer storage case in an aqueous solution of a coating agent, the surface of the wafer storage case is coated with the coating agent.

8. The process for preventing dust generation of a wafer storage case according to any of claims 3 to 7, wherein the wafer storage case to be coated with the coating agent is a cleaned wafer storage case.

9. The process for preventing dust generation of a wafer storage case according to claim 8, wherein the cleaned wafer storage case is a wafer storage case cleaned with surfactant cleaning and pure water cleaning.

10. The process for preventing dust generation of a wafer storage case according to any of claims 3 to 9, wherein the coating agent is a surfactant.

11. A wafer storing method comprising the steps of:
preparing wafers; and

2

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